

AMENDMENT TO THE CLAIMS

1.(Original) Method for the production of antifalsification identification elements each comprised of at least one layer reflecting electromagnetic waves, one spacer layer and one layer formed of metallic clusters, wherein onto a carrier substrate a partial or all-over layer reflecting electromagnetic waves and subsequently one or several partial and/or all-over polymeric layers of defined thickness are applied, whereupon onto the spacer layer a layer formed of metallic clusters is applied, which is produced by means of a method of vacuum technology or out of solvent-based systems.

2.(Original) Method for the production of antifalsification identification elements each comprised of at least one layer reflecting electromagnetic waves, one spacer layer and one layer formed of metallic clusters, wherein onto a carrier substrate a layer formed of metallic clusters is applied, which is produced by means of a method of vacuum technology or out of solvent-based systems, and subsequently one or several partial and/or all-over polymeric layers of defined thickness are applied, whereupon one partial or all-over layer reflecting electromagnetic waves is applied onto the spacer layer.

3.(Currently Amended) Method as claimed in ~~one of claims 1 or 2~~, characterized in that ~~onto claim 1, wherein~~ a first carrier substrate a layer reflecting electromagnetic waves and subsequently a polymeric spacer layer is applied, and onto a second carrier substrate a cluster layer, wherein, first, by connecting the two carrier substrates thus coated, the antifalsification identification element is generated or can be detected.

4.(Currently Amended) Method as claimed in ~~one of claims 1 to 3~~, characterized in that ~~onto claim 1, wherein~~ the cluster layer a protective layer is applied.

5.(Currently Amended) Method as claimed in ~~one of claims 1 to 4~~, characterized in that claim 1, wherein the layer onto which the spacer layer is applied, is modified by treatment with oxidizing fluids or by a PVD or CVD process.

6.(Currently Amended) Method as claimed in ~~one of claims 1 to 5~~, characterized in that claim 1, wherein the polymeric spacer layer is structured through decrosslinking effects.

7.(Original) Method as claimed in claim 6, characterized in that the decrosslinking structures of the structured polymeric spacer layer are converted into unique codes by means of fingerprint algorithms.

8.(Currently Amended) Method as claimed in ~~one of claims 1 to 7~~, characterized in that claim 1, wherein the polymeric spacer layer is modified by treatment with sodium hypochlorite, through a PVD or a CVD process.

9.(Currently Amended) Method as claimed in ~~one of claims 1 to 8~~, characterized in that claim 1, wherein the polymeric spacer layer comprises a chromophore.

10.(Currently Amended) Method as claimed in ~~one of claims 1 to 9~~, characterized in that claim 1, wherein the metallic cluster layer is deposited by sputtering or vapor deposition.

11.(New) Method as claimed in claim 2, wherein a first carrier substrate a layer reflecting electromagnetic waves and subsequently a polymeric spacer layer is applied, and onto a second carrier substrate a cluster layer, wherein, first, by connecting the two carrier substrates thus coated, the antifalsification identification element is generated or can be detected.